

UNITED STATES PATENT AND TRADEMARK OFFICE
CERTIFICATE OF CORRECTION

PATENT NO. : 7,535,220 B2
APPLICATION NO. : 10/597838
DATED : May 19, 2009
INVENTOR(S) : Yuiciro Sasaki et al.

Page 1 of 1

It is certified that error appears in the above-identified patent and that said Letters Patent is hereby corrected as shown below:

In Column 12, line 41 please delete “10. The beam control method according to claim 9, wherein the beam radiation method includes a radiation step which radiates the beam current which is controlled using the control parameters obtained in the control step of the beam in claim 12 to a material to be treated.” and insert therefor

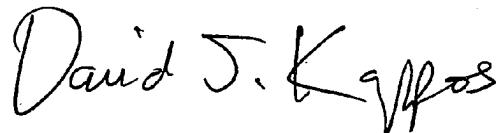
--10. The beam control method according to claim 9, wherein the beam radiation method includes a radiation step which radiates the beam current which is controlled using the control parameters obtained in the control step of the beam in claim 9 to a material to be treated.--

In Column 12, line 51 please delete “13. A material to be treated which is manufactured or inspected casing an ion injection device, an electronic beam exposure device, an accelerator or an electron beam vapor deposition device which includes the beam measuring device described in claim 1.” and insert therefor

--13. A material to be treated which is manufactured or inspected using an ion injection device, an electronic beam exposure device, an accelerator or an electron beam vapor deposition device which includes the beam measuring device described in claim 1.--

Signed and Sealed this

Thirteenth Day of July, 2010



David J. Kappos
Director of the United States Patent and Trademark Office